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(54) Title: CLEANING AGENT COMPOSITION, CLEANING AND PRODUCTION METHODS FOR SEMICONDUCTOR
WAFER, AND SEMICONDUCTOR WAFER

(57) Abstract: A cleaning agent composition comprising a nonionic surfactant represented by the following formula (I):
R1O(EO)x(PO)yH (I) (wherein R1 represents a linear or branched alkyl group having from 6 to 20 carbon atoms or a linear or
branched alkenyl group having from 6 to 20 carbon atoms, EO represents an oxyethylene group, PO represents an oxypropylene
group, EO and PO each is bonded by random addition or block addition, x number of EO's and y number of PO's are arranged in an
arbitrary order, x and y each independently represents an integer of 1 to 20, and x/(x+y) is 0.5 or more) and a quaternary ammonium
hydroxide) is provided. Also, Cleaning and production methods for semiconductor wafer using the cleaning agent composition,
and semiconductor wafer produced by the production method are provided.

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